

Scaling Effects on Ferro-Electrics: Application in Nanoelectronics and Characterization

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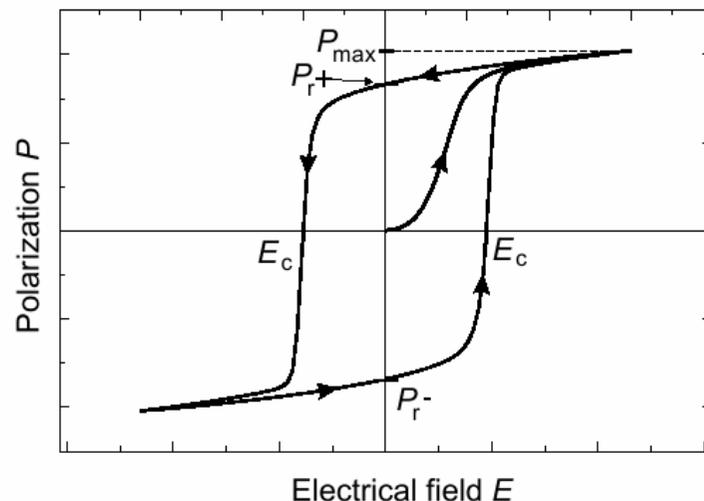
Université de Lyon

Ferroelectrics: dielectrics crystals which a spontaneous electric polarization due to atomic displacement in the crystal structure

The direction of polarization can be reoriented by an external electric field:

=> domains where the spontaneous polarization is parallel

=> hysteresis loops



Direction polarization can be used to store information: memories

Bit 0: Pr-

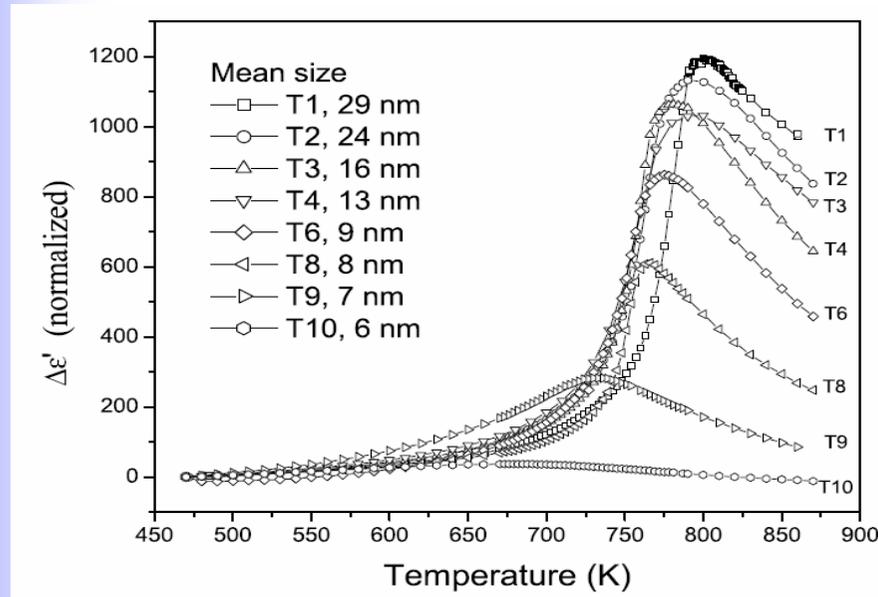
*2 atomic stable positions
in the crystal field*

Bit 1: Pr+

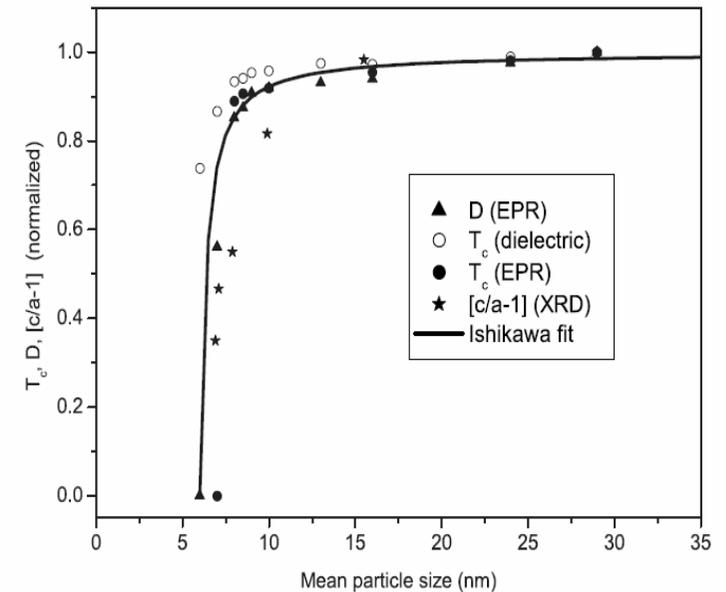
=> Non volatile data storage device

At nano-scale, strong influence of the surface energy, depolarization field, etc.

=> Modification of polarization, dielectric constant, Curie temperature, etc.



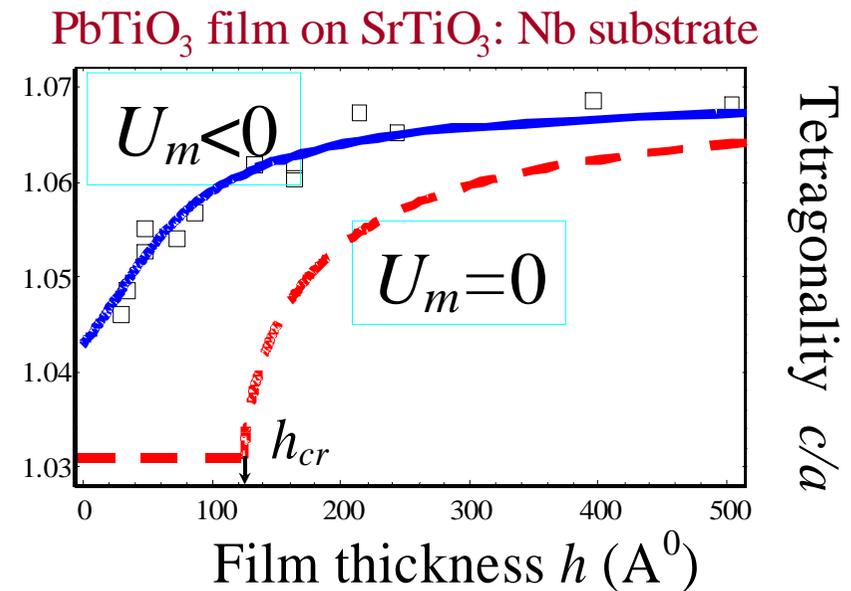
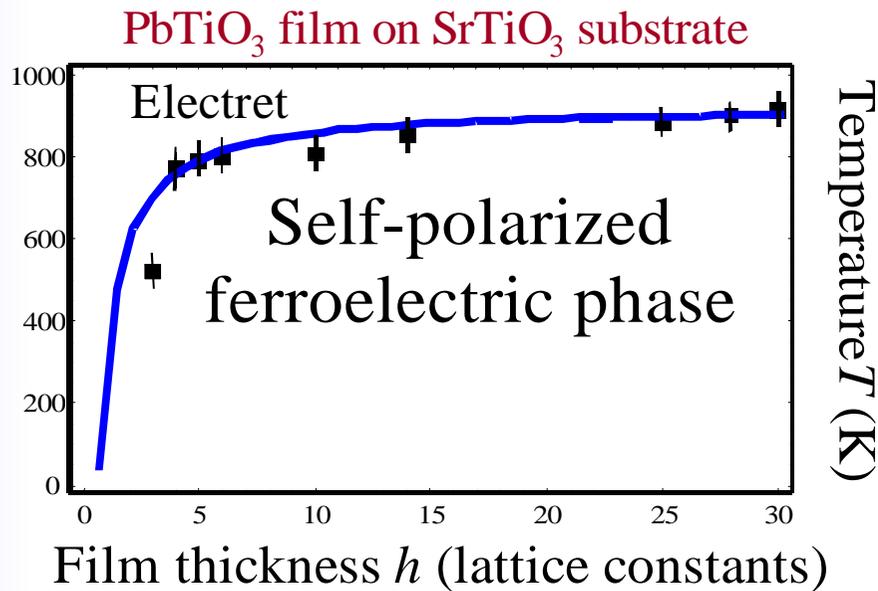
E. Erdem et al.,
J. Phys.: Condens. Matter **18**, 3861
 (2006)



What is the critical thickness to observe ferroelectricity in thin films?

Deformation of the film due to mismatch between the parameters of the film and substrate $U_m = (b - a)/b$ (a, b are their lattice constants) induce built-in electric field.

=> This field lead to electret state in thinner film.

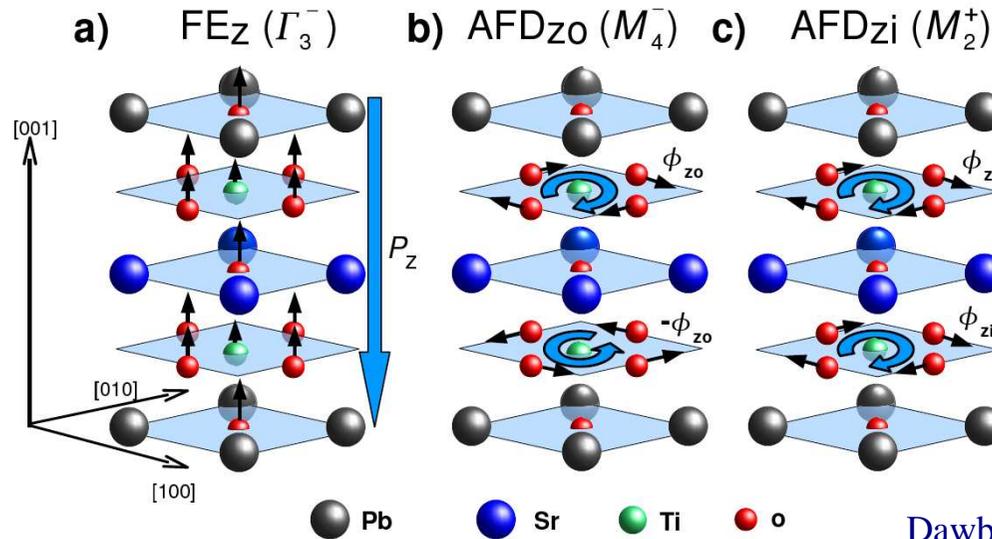
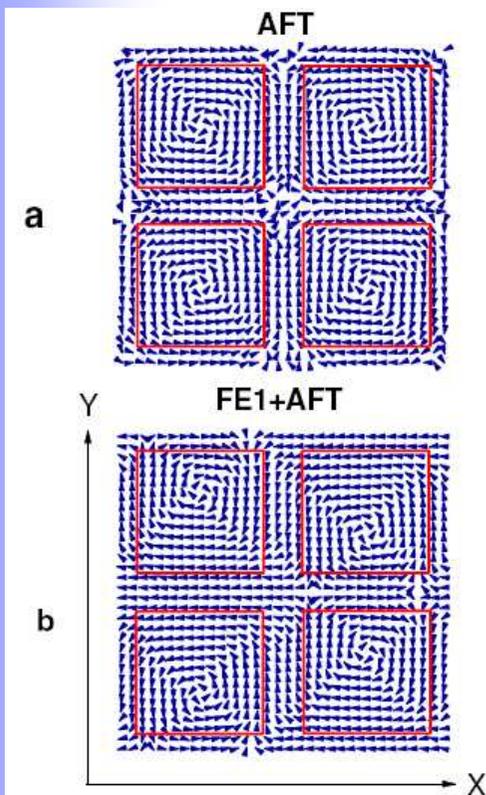


Glinchuk M.D., Morozovska A.N., Eliseev E.A., J. Appl. Phys. **99**, 114102 (2006)

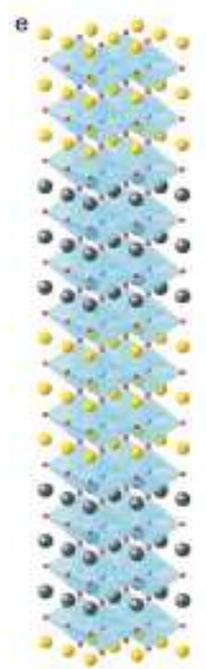
Triscone's group (Geneva): measurement of ferroelectricity down to 2.4 nm (PZT film) at room temperature.

However new properties absent in bulk materials appear in nano-ferroelectrics.

Superlattices of SrTiO_3 and $\text{PbTiO}_3 \Rightarrow$ Unusual polarization behaviour, modification of $T_c \dots$



Dawber, PRL 95 (2005)



Recent effort to predict properties of nano-ferroelectrics using *ab initio* models
Groups of Vanderbilt, Resta, Krakauer, etc.

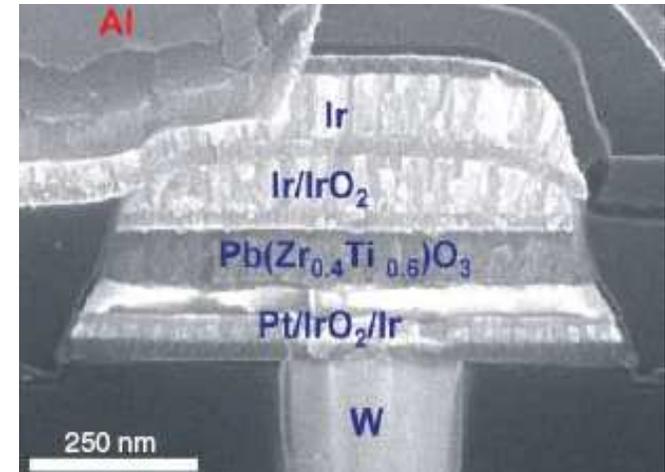
Polarization vortex in ferroelectric ABO_3 dots by Virtual Crystal Approximation (VCA)

Bellaiche, PRL 97 (2006)

Ferroelectric Random Access Memories: similar to DRAM but with a ferroelectric layer instead of a dielectric layer

Non volatile memories: data storage through the remnant polarization

Commercial production already at 350 nm (Fujitsu) and 130 nm (Texas Instrument)



32 Mb SAMSUNG FeRAM

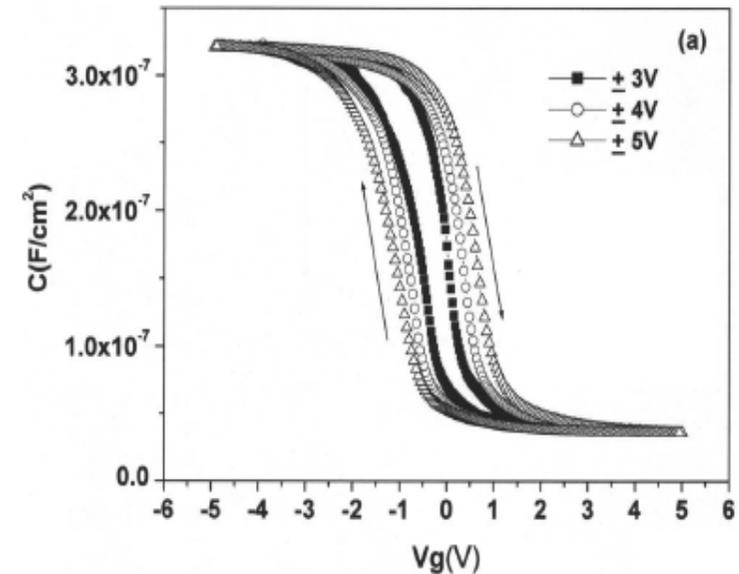
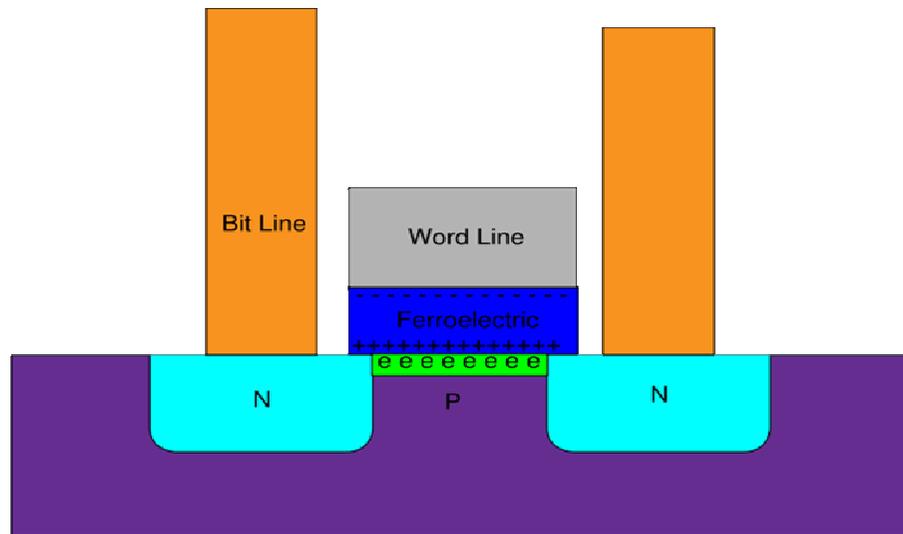
	SRAM*1	DRAM*2	EEPROM*3	FLASH*4	FRAM*5
Memory type	Volatile back-up	Volatile	Non-volatile	Non-volatile	Non-volatile
Cell structure	6T	1T/1C	2T	1T	1T/1C 2T/2C
Read cycle (ns)	12	70	200	70	110
Internal write voltage (V)	3.3	3.3	20 (supply voltage 3.3V)	12 (supply voltage 3.3V)	3.3
Write cycle	12ns	70ns	3ms	1 sec.	110ns
Data write	Overwrite	Overwrite	Erase + Write	Erase + Write	Overwrite
Data erase	Unnecessary	Unnecessary	Byte (64 byte page)	Sector (8K/16K/32K/64K)	Unnecessary
Endurance	∞	∞	1E5	1E5	1E10 to 1E12
Stand-by current (µA)	7	1,000	20	5	5
Read operation current (mA)	40	80	5	12	4
Write operation current (mA)	40	80	8	35	4

Notes: *1: 512K × 8bit *2: 2M × 8bit *3: 8K × 8bit *4: 1M × 8bit *5: 8K × 8bit

Same functionality as Flash Memories but:

- Lower power usage
- Faster write performance
- Greater maximum of cycles

Ferroelectric Field Effect Transistor: similar to MOSFET, the gate oxide is a ferroelectric



Depending on remnant polarization, electrons are depleted or accumulated

Non volatile memories

Decrease of **stand-by loss** (« vampire power »)

Only few perovskite oxides (big class of ferroelectric materials) are suitable for growth on silicon

From 2D film to 1D dots:

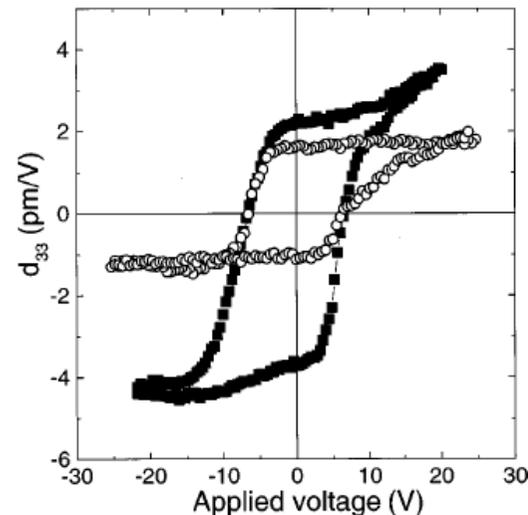
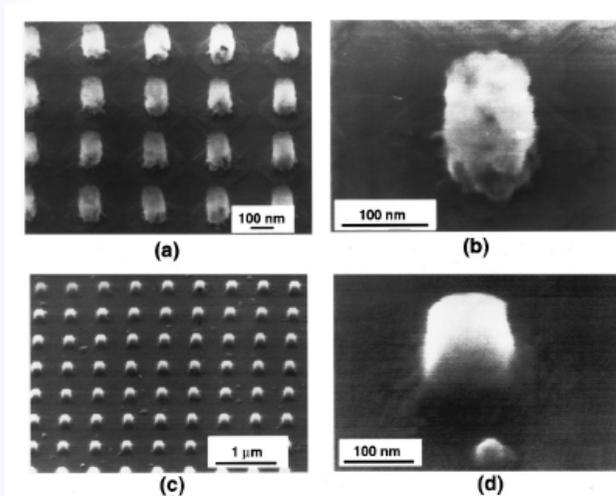
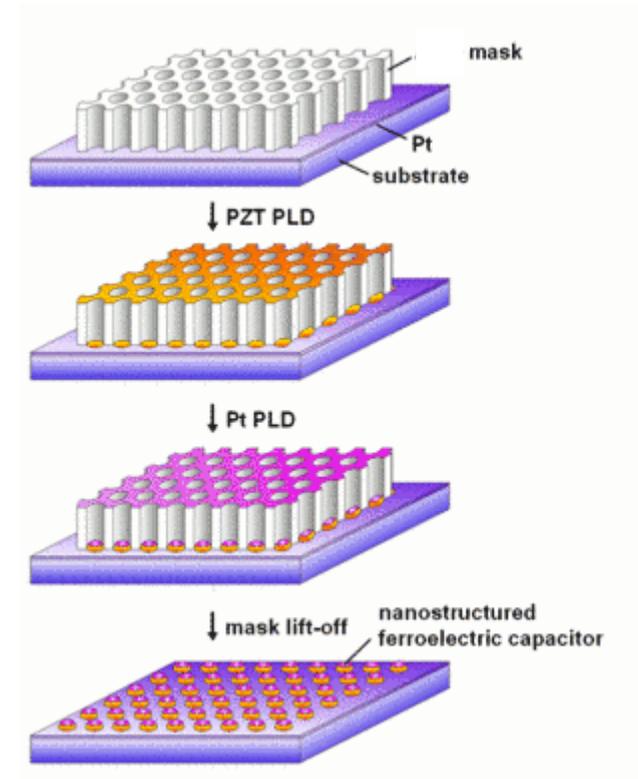
Focused Ion Beam etching, e-beam lithography, imprint

High-precision positioning

Size control but limited in resolution

Damage the nano-structures (layer ~10 nm)

Time-consuming



M. Alexe, Appl. Phys. Lett. 75, 1999

Self-assembled process:

Formation of arrays of ferroelectric nano-crystals on a substrate

As for semi-conductor quantum dots growth, balance between interface, substrate and film energies

Avoid the processing damage during FIB patterning

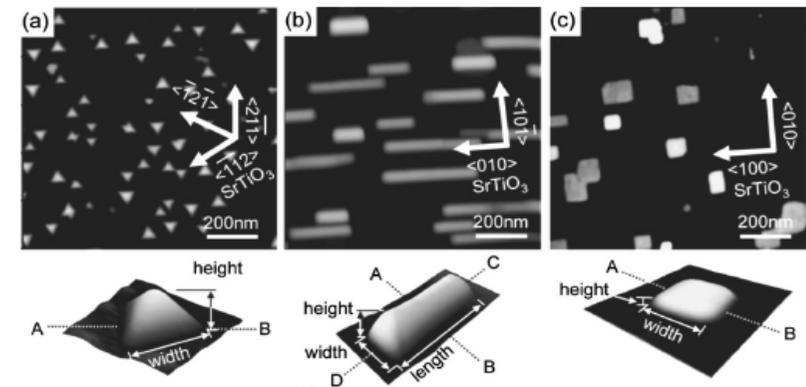
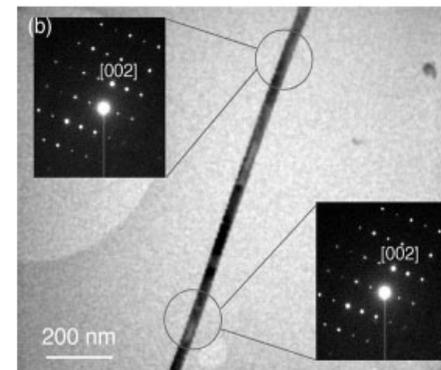
Smaller dimensions structures than those obtained with top-down processes

Nano-wires fabrication:

Hydro-thermal decomposition of bimetallic precursor

Well-isolated single-crystalline BaTiO_3 rods with diameters from 5 to 60 nm and several μm -long

Park, Adv. Mat. 15, 2003



PbTiO_3 grown on SrTiO_3 with different crystalline orientations

Nomura, Appl. Phys. Lett. 86, 2005

The AFM as a tool for electric characterization at the nanoscale :

A conductive tip can => a nanometric electrode

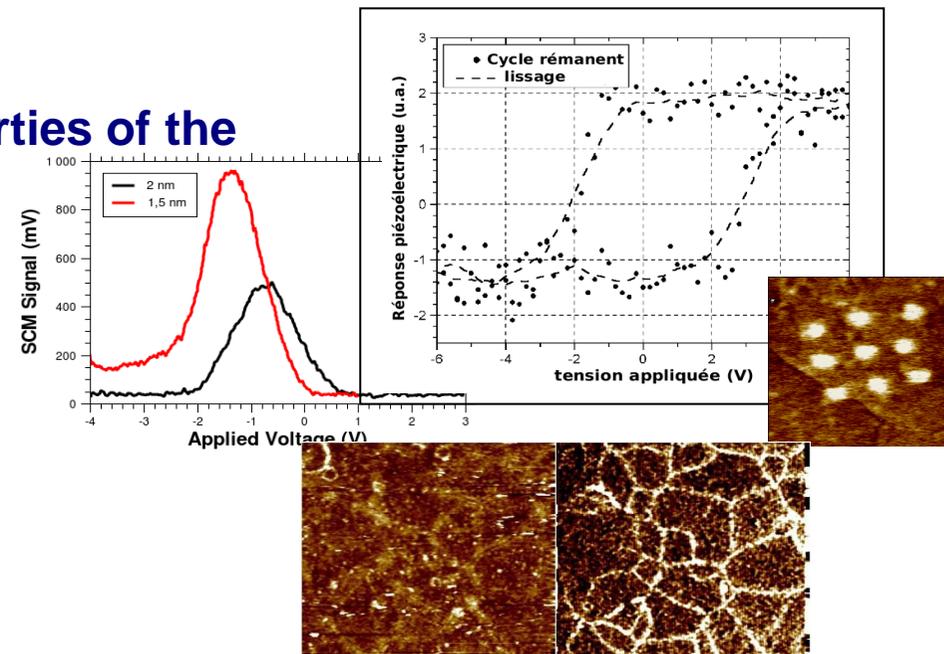
Piezoelectric motion controller => **positioning** with a nanometric resolution

Examples :

- Electric Force Microscopy (**EFM** : electric field)
- Kelvin Force Microscopy (**KFM** : potential)

Characterization of the electrical properties of the dielectrics and ferroelectrics:

- Current measurements
- Capacitive measurements
- Piezoelectric measurements



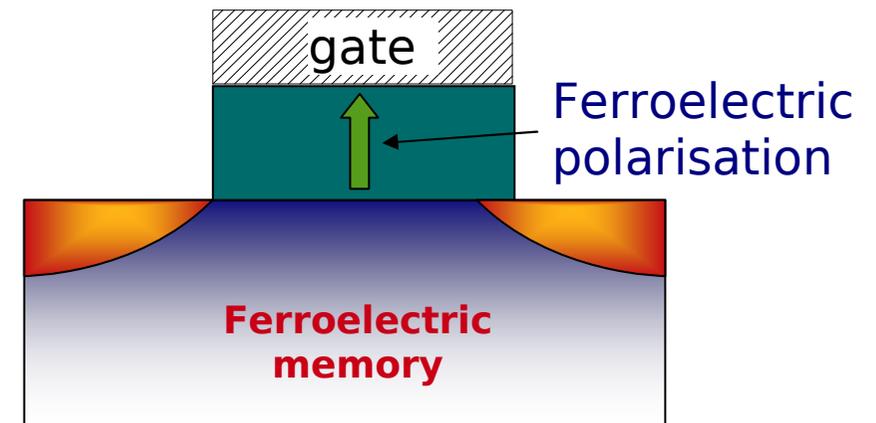
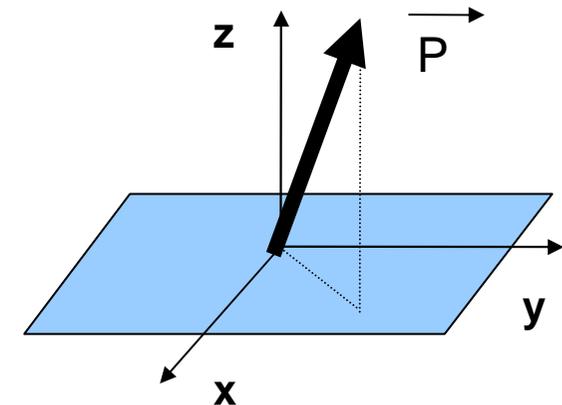
Numerous size effects are expected in ferroelectrics materials :

- Coercive voltages □
- Remnant polarisation □
- Dielectric constant □
- Smallest domain size ?
- Smallest thickness allowing ferroelectricity ?
- Piezoelectric constants □

Must be measured at the nanoscale

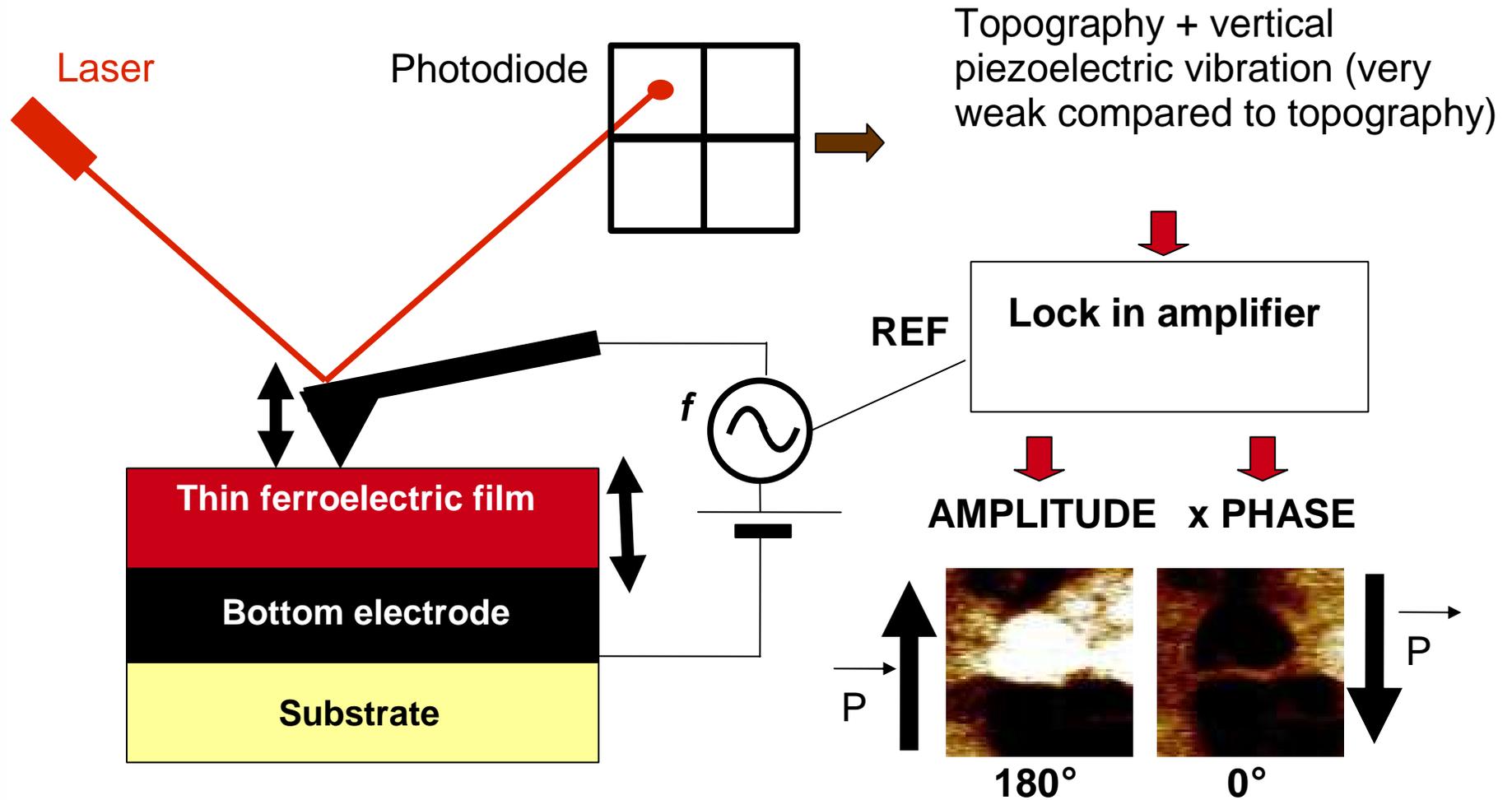
The reduction of the size of devices using ferroelectric layers is a challenging problem for characterization

Characterization provides crucial feed back to growers

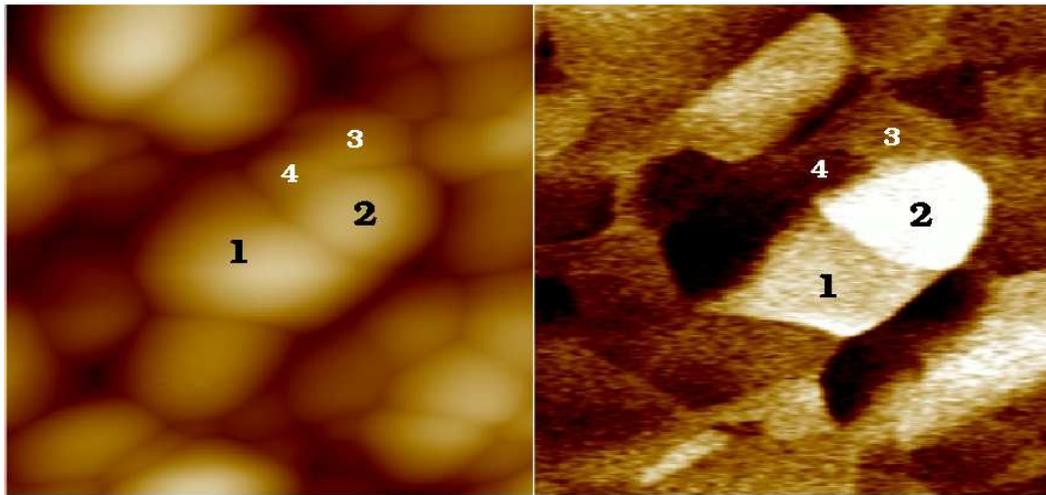


Inverse piezoelectric effect => vibration of the surface due to the application of an alternating voltage.

All ferroelectrics are piezoelectric



Antiparallel domains vibrate with an opposite phase



Mapping of ferroelectric domains
(component **perpendicular** to the surface) in LiNbO_3 . The spatial resolution is nanometric.

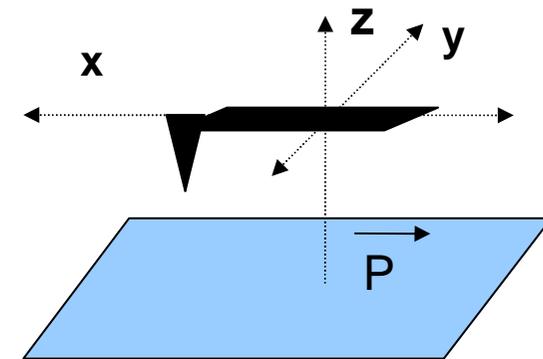
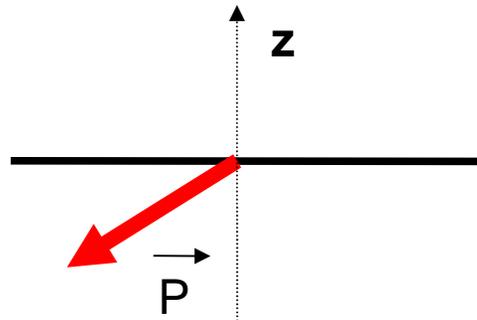
B. Gautier, V. Bornand, Thin Solid Films 515(4-5):1592, 2006

out of-plane

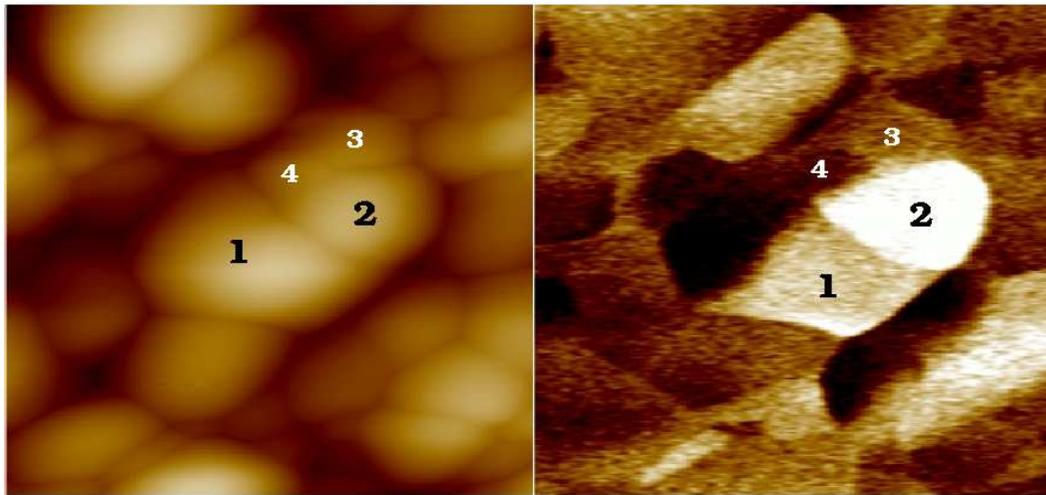


in-plane

The **in-plane** component in the y-direction is also accessible

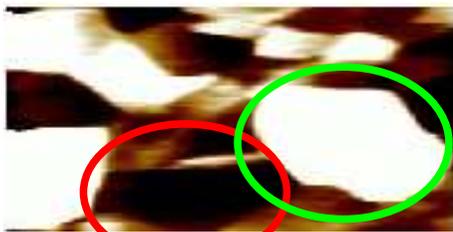
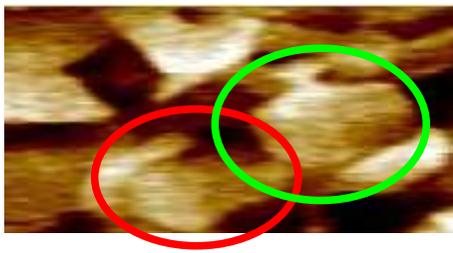


The in-plane component **parallel** to the cantilever (x direction) remains inaccessible



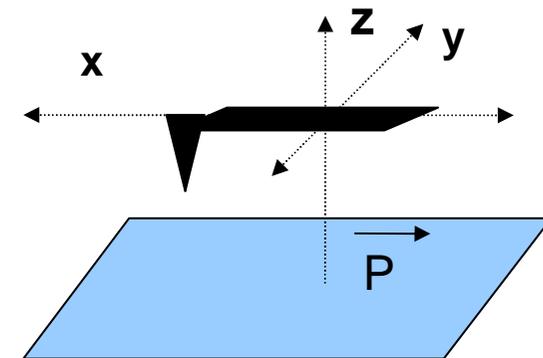
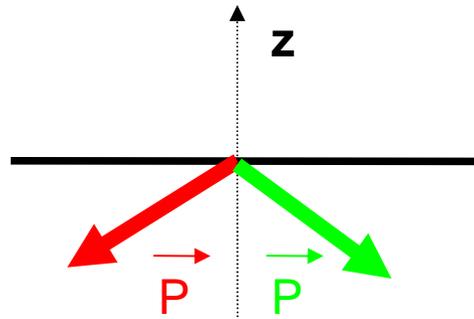
Mapping of ferroelectric domains
(component **perpendicular** to the surface) in **LiNbO₃**. The spatial resolution is nanometric.

out of-plane

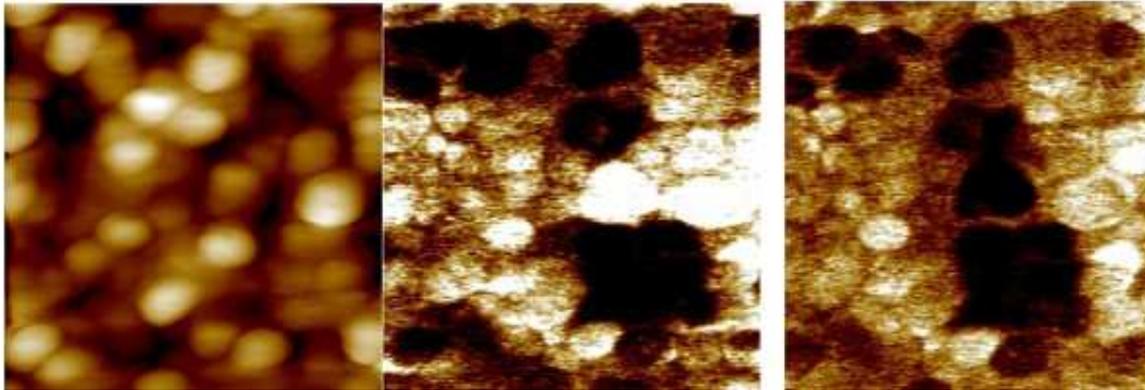


in-plane

The **in-plane** component in the **y**-direction is also accessible



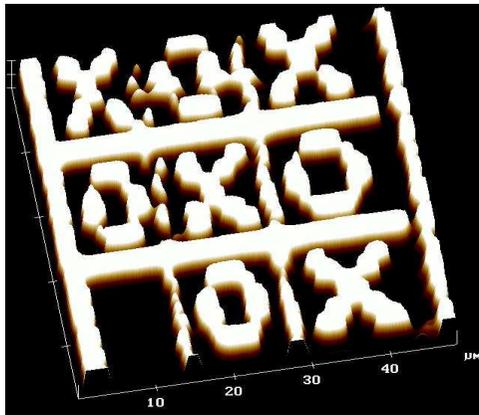
The in-plane component **parallel** to the cantilever (**x** direction) remains inaccessible



Local switching

of the polarisation by applying a sufficient voltage between the tip and the sample (here ≈ 10 V)

C. Thiebaud, D. Charraut, B. Gautier, J.C. Labrune, Ann. Chim. ScL Mat, 26:145 (2001)

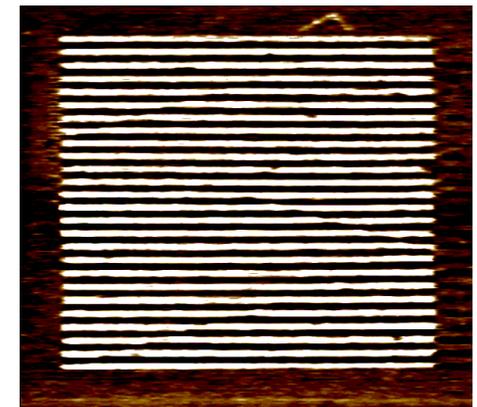
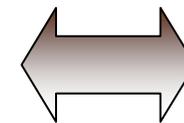
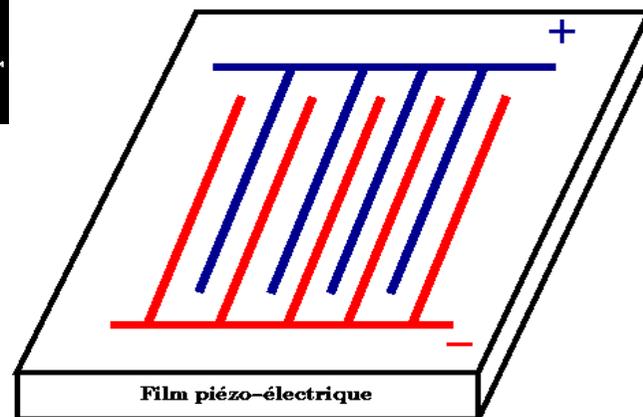


Creation of any polarisation pattern

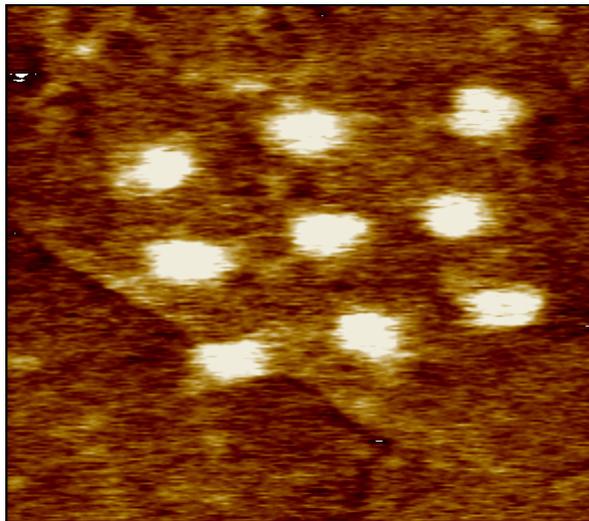
Applications for the Surface Acoustic Waves Devices (SAW)
=> replacement of the top electrodes

$$f \sim \frac{V_R}{T}$$

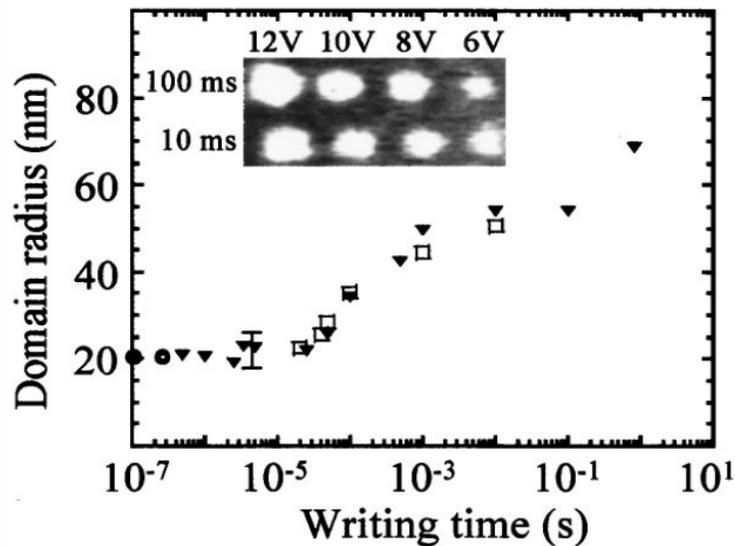
=> 20 Ghz
T= 200 nm



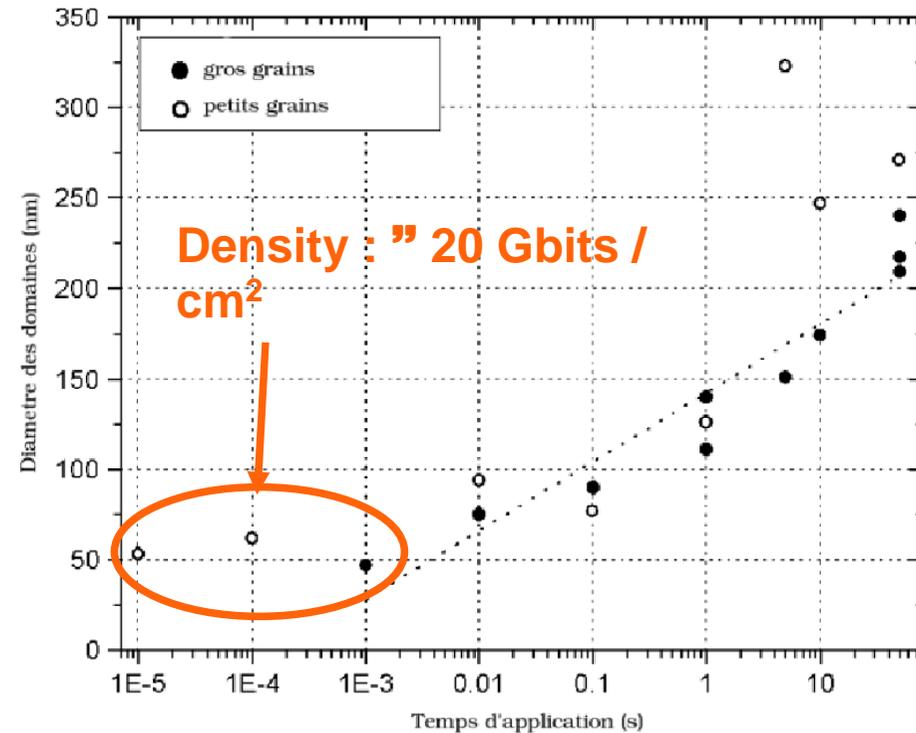
S. Ballandras, B. Gautier, D. Hauden and J.-C. Labrune.
Patent USA – Canada - Europe 0009246, 2001.



Microstructure of the film, voltage amplitude, duration, geometry... influence the final size of the domain => density of integration of the final device



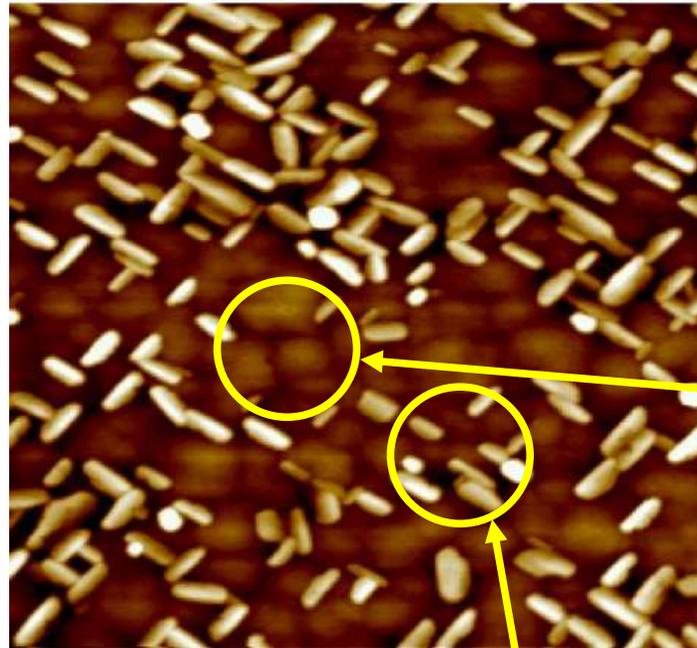
P. Paruch et al. Appl. Phys. Lett., Vol. 79, No. 4, 23 (2001)



Evolution of the domain size with the duration of the voltage pulse

B. Gautier, C. Soyer, E. Cattan, D. Remiens and J.-C. Labrune
Integrated Ferroelectrics 269:219, 2002

PFM allows to test a very small area of the film with **piezoelectric hysteresis loops** => test of the ferroelectric nature of the film

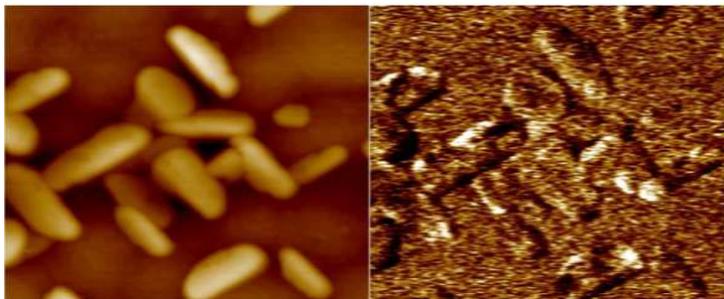
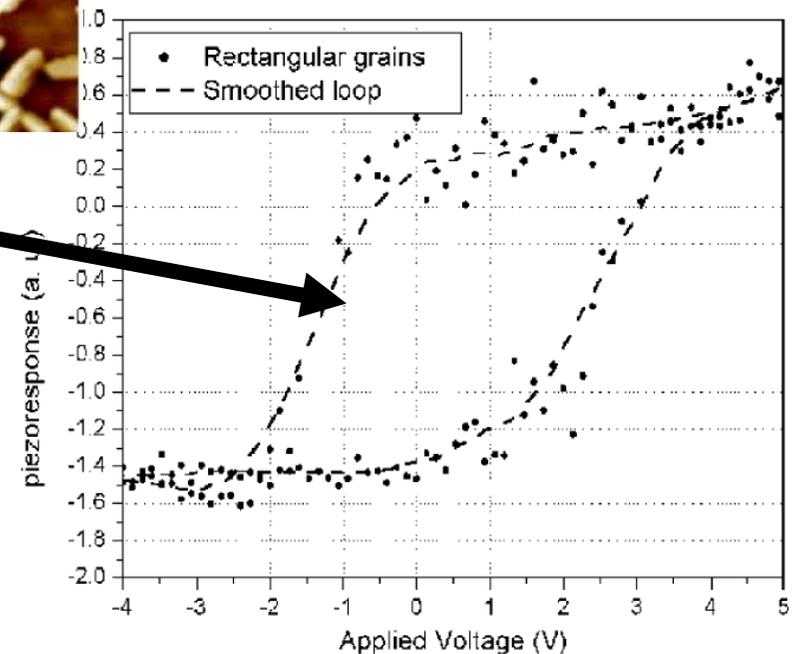


3 microns

<115> Direction

Local piezoelectric hysteresis loops (here on a $\text{SrBi}_2\text{Nb}_2\text{O}_9$ thin film), **only** on the <115> regions of the film

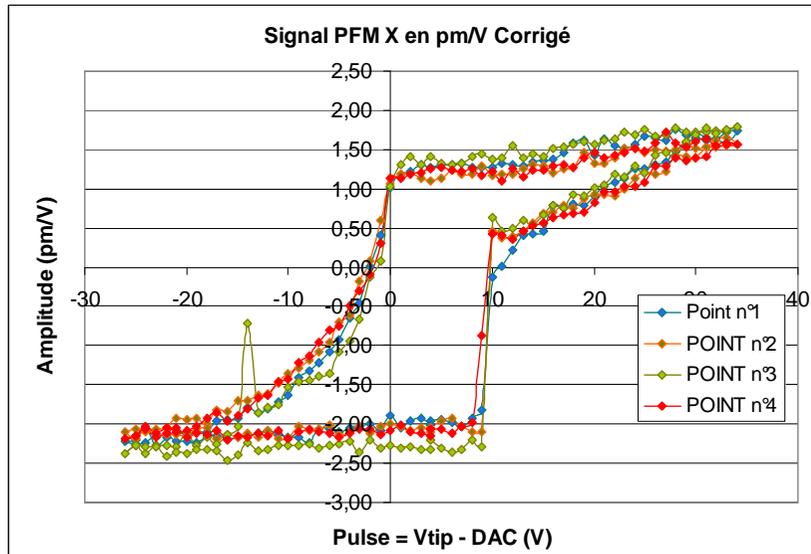
<001> Direction



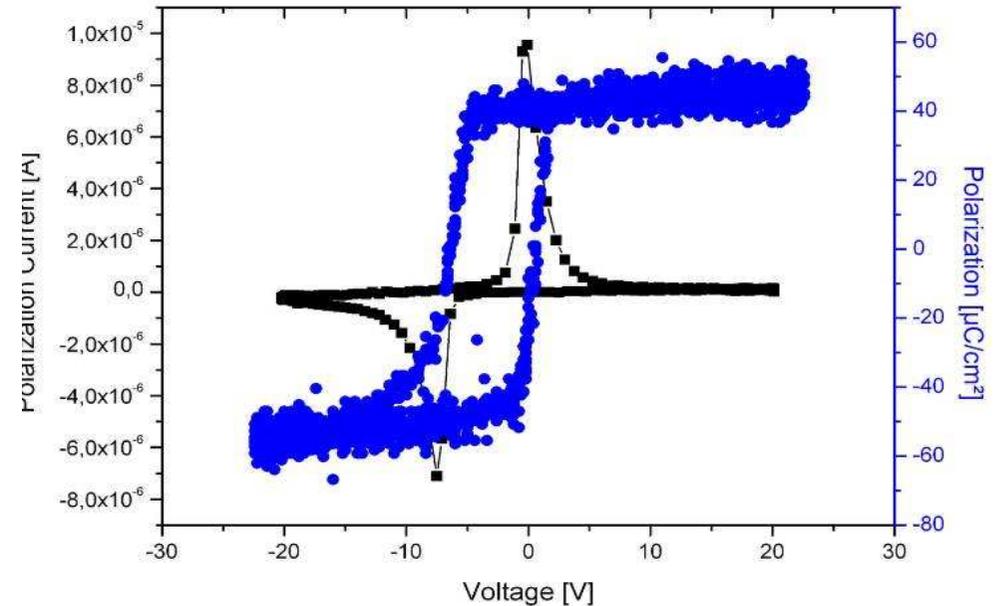
B. Gautier, Jean-Rene Duclere, and Marilyn Guilloux-Viry Appl. Surf. Sci. 217:107, 2003
J.-R. Duclère, M. Guilloux-Viry, A. Perrin, and B. Gautier, Ann. Phys. 13(1-2):35, 2004

Ferroelectric memories : orientation must be perpendicular to the surface => Smart-Cut™ technology.

One explanation for the back-switching of the domains : **imprint**



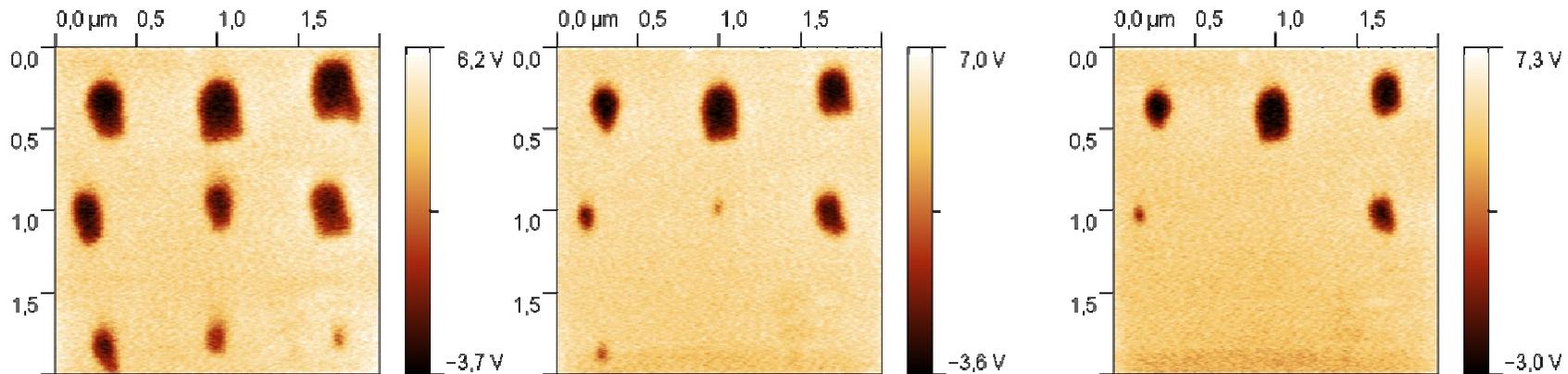
Hysteresis loops performed by PFM : a strong imprint is recorded (shift of the loop toward positive voltages). Courtesy A. Brugère.



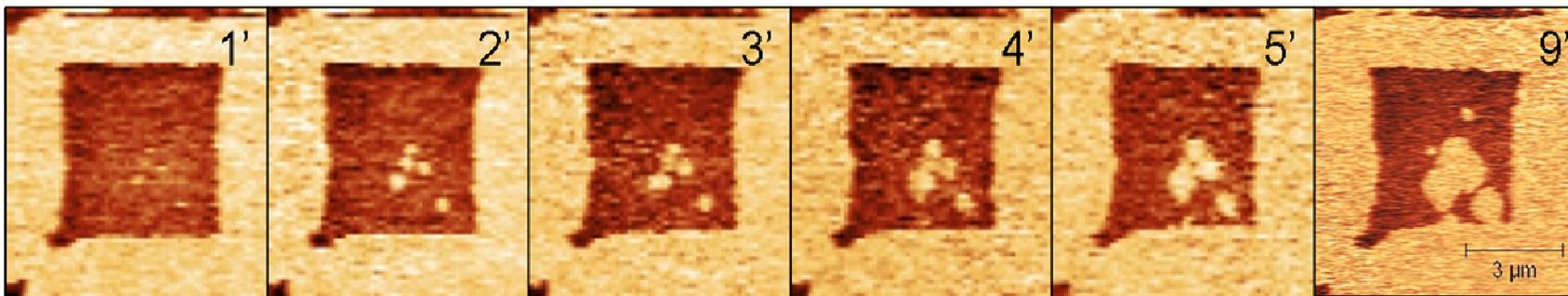
Hysteresis loops performed by a Sawyer-Tower circuit (polarisation and current) : the same imprint is found (voltage applied on the sample and not on the tip as for PFM). Courtesy J.S. Moulet.

=> Reliable information provided by the PFM mode

Example of LiTaO_3 (LTO)



5 V offset is applied during PFM measurements
Images : A. Brugère, CEA



Domains written with voltage pulses of different amplitude and duration in a thin film ($e \sim 120$ nm) of LiTaO_3 (LTO) obtained by Smart-CutTM (sample from SOITEC, Grenoble) : depending on their size, the domains flip back to a preferential state. Below : domains flip back even after uniform polarisation of a large area. The flip back phenomenon seems to start from « seeds »

=> application to the fatigue of ferroelectric layers

Nano-ferroelectrics high density memories are of major interest

It leads to challenging understanding and simulation of the properties of such materials at nanoscale

Piezoresponse Force Microscopy (PFM) is a very powerful tool to investigate the ferroelectric and piezoelectric nature of thin films and monocrystals at the nanoscale.

It allows to probe the **dynamic behaviour** of ferroelectric domains => e.g. fatigue phenomena at the nanoscale

PFM is in some cases the only way to probe the ferroelectric nature of a surface (heterogeneous surfaces, nanostructures...).

The **same apparatus** is used to read and write ferroelectric domains – any polarisation pattern can be written with a resolution of several tens of nanometers.

Thanks to:

Antoine BRUGERE (CEA, Grenoble), Serge GIDON (CEA, Grenoble) Jean-Sébastien MOULET (LTFC-SOITEC, Grenoble), Emmanuel DEFAY (CEA/LETI, Grenoble), Veronique BORNAND (Univ. Montpellier 2), J.R. Duclère (Univ. Limoges), Jean-Luc MAURICE (Thalès, Palaiseau), Gang NIU (INL, Lyon), Octavian LIGOR (INL, Lyon), Wael HOURANI (INL, Lyon), Guillaume SAINT-GIRONS (INL, Lyon), Guy HOLLINGER (INL, Lyon)

Thank you for your attention